



L. Number	Hits	Search Text	DB	Time stamp
1	2	((dielectric insulating) near film) and ((pore porous void) near (monodisperse monodispersed monodispersion monodispersion))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:25
2	18	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm)))))) and ((first second) near phase)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:25
3	63	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm)))))) and lattice	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:25
4	70	(((((dielectric insulating) near film) and (pore porous void)) and (dielectric near constant)) and (nanoparticle ((particle powder) same (nanometer nanometere nm)))))) and (silsesquioxane polyorganosilsesquioxane organosilsesquioxane organopolysilsesquioxane polysilsesquioxane methylsilsesquioxane hydrogensilsesquioxane phenylsilsesquioxane polyhydrogensilsesquioxane hydrogenpolysilsesquioxane polymethylsilsesquioxane methylpolysilsesquioxane polyphenylsilsesquioxane phenylpolysilsesquioxane)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:26
5	2	((suspension same (water near soluble) same (oxide silica ((germanium silicon) adj dioxide)) same particle) same (surface near (treated modified treating modifying treat modify coat coated coating))) and ((dielectric insulating) same binder)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:26
6	131	((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:26
7	15	((dielectric insulating) near (binder film)) and (((particle powder) same (void pore)) same (nanometer nanometere nm)) same ((uniform uniformly equal equally) near (space spaced separated distribute distributed distributing separate dispersed disperse)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:27
8	131	((dielectric insulating) near film) and (((particle powder) same (void pore)) same (nanometer nanometere nm))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:27
9	17	((particle powder) same (void pore)) same (nanometer nanometere nm)) and ("3-D" 3d "three-dimensional" "3-dimensional" (three near dimensnional)) near lattice)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:27
10	17	((particle powder) same (void pore)) same (nanometer nanometere nm)) and ("3-D" 3d "three-dimensional" "3-dimensional" (three near dimensnional)) near lattice)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:28
11	9	((dielectric insulating) near film) and ("3-D" 3d "three-dimensional" "3-dimensional" (three near dimensnional)) near lattice)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:28
12	16	428,447,116,304.4,308.4,312.2,312.6,315.7,318.4,319.1,319.3,332,450,209,449,477,387,1 and ("3-D" 3d "three-dimensional" "3-dimensional" (three near dimensnional)) near lattice)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:28
13	21	((particle powder) same (void pore)) same (nanometer nanometere nm)) and ((curing cured cure crosslink crosslinking crosslinked harden hardening hardened vulcanize vulcanizing vulcanized) same (oven furnace) same (inert n?sub.2 he! Ar! nitrogen helium argon))) and ((dielectric insulating) near film) and ((curing cured cure crosslink crosslinking crosslinked harden hardening hardened vulcanize vulcanizing vulcanized) same (oven furnace) same (inert n?sub.2 he! Ar! nitrogen helium argon)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/12 07:29

